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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/611,985	07/03/2003	Akira Hokazono	239757US-2 DIV	4179
22850	7590 08/12/2004		EXAMINER	
OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET			NGUYEN, CUONG QUANG	
	RIA, VA 22314		ART UNIT PAPER NUMBER	
			2811	
			DATE MAILED: 08/12/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	10/611,985	HOKAZONO ET AL.					
Office Action Summary	Examiner	Art Unit					
	Cuong Q Nguyen	2811	A~				
The MAILING DATE of this communication app Period for Reply A SHORTENED STATUTORY PERIOD FOR REPLY		•	ess				
THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply if NO period for reply is specified above, the maximum statutory period w. - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	within the statutory minimum of thirty (30) days rill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONED	s will be considered timely. the mailing date of this comr D (35 U.S.C. § 133).	munication.				
Status							
1) Responsive to communication(s) filed on	<u>_</u> .						
2a) ☐ This action is FINAL . 2b) ☑ This	☐ This action is FINAL . 2b) ☐ This action is non-final.						
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	93 O.G. 213.					
Disposition of Claims							
4)⊠ Claim(s) <u>1-18</u> is/are pending in the application.							
4a) Of the above claim(s) is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>11 and 16-18</u> is/are rejected.							
7) Claim(s) <u>12-15</u> is/are objected to.							
8) Claim(s) are subject to restriction and/or	r election requirement.						
Application Papers							
9) The specification is objected to by the Examine	r.						
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority under 35 U.S.C. § 119			·				
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)⊠ All b)□ Some * c)□ None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No. 10/076, 497 3. Copies of the certified copies of the priority documents have been received in this National Stage							
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).							
* See the attached detailed Office action for a list of the certified copies not received.							
	·						
Attachment(s) 1) Notice of References Cited (PTO-892)	4) Theories Cummen	(PTO 413)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date							
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date <u>07-05-05</u>	5) Notice of Informal P 6) Other:	atent Application (PTO-1	52)				
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DETAILED ACTION

Specification

1. A new title is required that is clearly indicative of the invention to which the claims are directed.

Claim Rejections - 35 USC § 112

2. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 17 and 18 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. It is unclear how "forming an epitaxial on said second diffusion layer by the epitaxial growth" as claimed in claim 17 when "selectively forming an epitaxial layer only on said first diffusion layer" as claimed in claim 11.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

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Claim 11 is rejected under 35 U.S.C. 102() as being anticipated by Lee (US 6,455,366).

Lee discloses a method of manufacturing a semiconductor device comprising: forming a first gate electrode on a first semiconductor layer in a first region (c) of a semiconductor substrate (21), and a second gate electrode on a second semiconductor layer in a second region of the semiconductor substrate; forming a first diffusion layer (28) in the first semiconductor layer using the first gate electrode as a mask, and a second diffusion layer (38) in the second semiconductor layer using the second gate electrode as a mask; and selectively forming an epitaxial layer (27) only on the first diffusion layer. See Fig.2A-Fig.2E.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all 4. obviousness rejections set forth in this Office action:

A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 16 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lee in view of Chau et al. (US 6,165,826).

Lee teaches all the limitations of claim 11 as shown above. However, Lee does not teach that the method comprises a step of forming silicide layer by performing silidation of the surface of source/drain regions.

Chau discloses a method of manufacturing of a semiconductor device comprising a step of forming a silicide layer on the sourcee/drain regions. See Fig.5F.

It would have been obvious to one of ordinary skill in the art to form a silicide layer on the surface of first and second source/drain regions as taught by Chau into Lee's device in order to reduce the contact resistance of the fabricated transistor. See Chau's col.19 lines 59-62.

Allowable Subject Matter

- 5. Claims 12, 13, 14, and 15 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- The following is an examiner's statement of reasons for allowance: Tigelaar et al. appears to be the closest prior art reference. However, this reference fails to teach the following: an etching stop layer overlying isolation layer (claim 4); the etching layer within the trench (claim 5); means for connection including an aperture, wherein selected ones of plurality of conductive films are recessed from a perimeter of the aperture and insulating material between perimeter of aperture and recessed surfaces selected ones of plurality of conductive films (claim 6); different materials are oppositely doped semiconductor materials, wherein means for selectively forming connections

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includes doped semiconductor studs respectively forming connections and blocking diodes with conductive films (claim 8). Prior art of record fails to teach or suggest to incorporate these limitations into Tigelaar et al. to arrive at the claimed device.

Conclusion

- Papers related to this application may be submitted to Technology center (TC) 2800 by facsimile transmission. Papers should be faxed to TC 2800 via the TC 2800 Fax center located in Crystal Plaza 4, room 4-C23. The faxing of such papers must conform with the notice published in the Official Gazette, 1096 OG 30 (November 15, 1989). The Group 2811 Fax Center number is (703) 872-9306. The Group 2811 Fax Center is to be used only for papers related to Group 2811 applications.
- 8. Any inquiry concerning this communication or any earlier communication from the Examiner should be directed to CUONG Q NGUYEN whose telephone number is (571) 272-1661. The Examiner is in the Office generally between the hours of 6:30 AM to 5:00 PM (Eastern Standard Time) Monday through Thursday.
- 9. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor Eddie Lee who can be reached on (571) 272-1732.
- 10. Any inquiry of a general nature or relating to the status of this application should be directed to the Technology Center Receptionists whose telephone number is 308-0956.

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Cuong Nguyen

Primary examiner

8/5/04